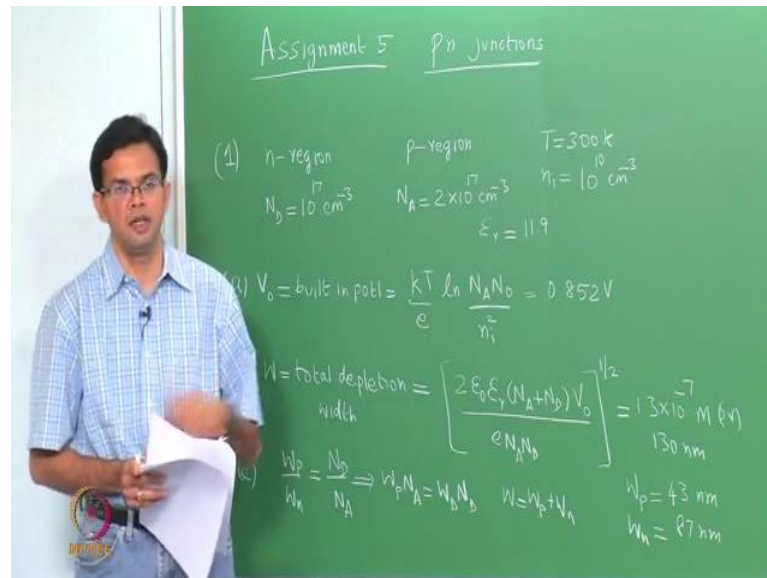


**Electroinic Materials, Devices And Fabrication**  
**Prof. Dr. S Parasuraman**  
**Department of Metallurgical And Materials Engineering**  
**Indian Institute of Technology, Madras**

**Lecture - 17**  
**Assignment 5 - Pn Junctions**

(Refer Slide Time: 00:26)



In today's assignment we are going to look at pn junctions. This is assignment 5. In assignment 4 we looked at metal semi-conductor junctions. In assignment 5, we are going to look junctions form between p and N type. So, uaually tha p and N are of same material which it is a homo junction. We also seen hetro junctions were the junction is found between 2 different materilas. In this assignment we will focus fully on the homo junctions. We will do some calculations on built in potential when a junction is formed. The depletion width and the that is the total depletion width and also the depletion width on p and the N side. A p N junction is essentially a diode it is a rectifier.

So, that it conducts current in the forward bias and does not conduct in the reverse bias. So, we will also do some calculations of the forward bias current and reverse saturation current. So, some of this will similar to what we did in assignment 4, where we looked at a short key junction which is also a rectifier. So, later compare the properties of a p N junction in that of schottky junction. So, let me go to problem number 1.

We have a silicon p N junction which has an N region with 10 to the 17 donors per

centimeter cube N region. So,  $N_d$  is  $10^{17}$  centimeter per cube. And there is p region with accepted concentration of  $2 \times 10^{17}$  centimeter per cube N a the material here silicon and it is at room temperature. So, temperature T is 300 kelvin the intrinsic carrier concentration, we have seen this so many times in the past, is just  $10^{10}$  to the 10 centimeter per cube.

So, in part a we want to calculate the built in potential of this junction. So,  $V_{naught}$  is the built in potential. So, it is the potential when the junction is an equilibrium. And this forms, because we have electrons from the N side moving into the p side. This is a diffusion current, we have wholes from the p side moving to the N side. These essentially meet each other and annihilate. So, that you have depletion region.

So, on one side of the depletion region you have a net positive charge. This is the N side on the other side you have a net negative charge that's your p side. And there is a junction potential that develops. So, this built in potential is nothing but  $\frac{kT}{e} \ln \frac{N_a N_d}{n_i^2}$ . So, this is just direct substitution of the numbers  $N_a$  and  $N_d$  are given  $n_i^2$  is also given.

If  $n_i$  is not known can always calculate  $n_i$  from the gap and the effective density of states or the effective mass electrons and holes. So, we just plug in the numbers and the answer 0.852 volts. In part 2, we want to calculate the total depletion width, let me call the  $w$  that is the total depletion width. So, depletion width again forms because we have electrons and wholes moving across the junction and the recombining.

So, saying this concept of depletion width earlier when we look at a short key at a short key junction in that case the depletion width is almost entirely on the semiconductor side. So, here depletion width will be in both the p and the N side. So, total depletion width again its given by a direct formula substitution  $2 \sqrt{\frac{\epsilon N_a N_d}{e} V_{naught}}$  where  $V_{naught}$  is your built in potential by  $e N_a$  and  $N_d$  and whole to the 1 half.

So,  $\epsilon$  is the permittivity of free space  $\epsilon_r$  is the permittivity of silicon the relative permittivity and  $\epsilon_r$  is 11.9. So, it is the known value of silicon. So, once again everything here is known we just calculated the built in potential  $V_{naught}$ . So, that we can do the substitution and this works out to be  $1.3 \times 10^{-7}$  meters or you want to write in nanometers 130 nanometers.

In part c, we want to calculate the depletion width on the p and the N side. So, the ratio of depletion widths  $W_p$  over  $W_n$  is inversely proportional to the concentration of your dopants. So, this is equal to  $N_d$  over  $N_a$  another way of writing off course is  $W_p N_a$  is  $W_n N_d$  and this comes from the charge neutrality. So, that the total positive charge due to your positively charged donors on the N side must be equal to the total negative charge due to the negatively charged accepted ions on the p side. And those two are essentially balanced. We also know the total width  $w$  is  $W_p$  plus  $W_n$  and total width  $W$  has been calculated to be 130 nanometers.



So, we have all the numbers, is again a case of doing the substitution and the math. So, I will just write down the final values. So,  $W_p$  is 43 nanometers and  $W_n$  is 87 nanometers. So, the total width comes out to be 130 nanometers, the accepted concentration on the p side is higher. So, 2 times 10 to the seventeen. So, the depletion width on the p side is smaller. So, let us to now go problem 2.

(Refer Slide Time: 08:46)

**Problem #2**

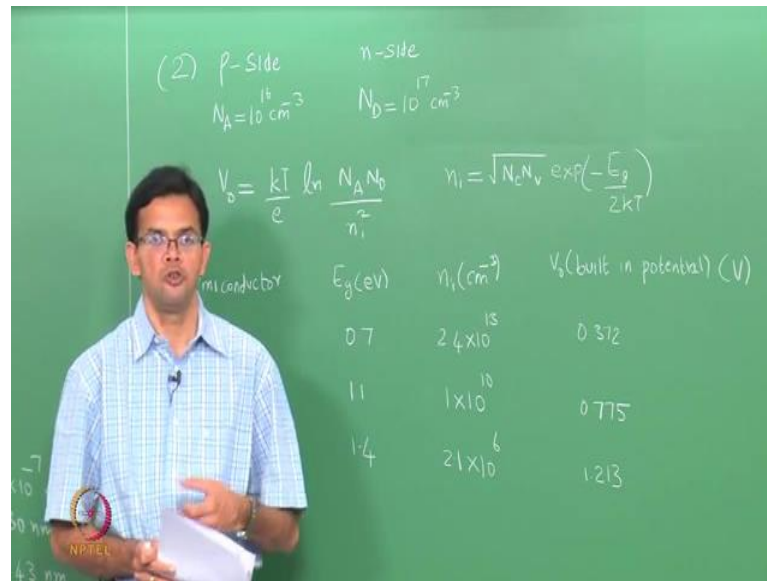
A pn junction diode has a concentration of  $10^{16}$  acceptor atoms  $\text{cm}^{-3}$  on the p-side and  $10^{17}$  donor atoms  $\text{cm}^{-3}$  on the n side. What will be the built-in potential for the semiconducting materials Ge, Si, and GaAs?

Semiconductor	$E_g$ (eV)	$n_i$ ( $\text{cm}^{-3}$ )
Ge	0.7	$2.40 \times 10^{13}$
Si	1.1	$1.0 \times 10^{10}$
GaAs	1.4	$2.1 \times 10^6$


Electronic materials, devices, and fabrication


Problem 2, we have a p n junction diode with the concentration of 10 to the 16 accepted atoms on the p side and 10 to the 17 donor atoms on n side.

(Refer Slide Time: 09:05)



So, once again you have p side and the n side. So,  $N_A$  is  $10^{16}$  and  $N_D$  is  $10^{17}$  per centimeter cube. So, we need to know the built in potential if the material of the semiconductor is different. So, in this particular case we want the built in potential for semiconductor materials germanium, silicon and gallium arsenite. So, if you go back to the formula for the built in potentials  $\frac{kT}{e} \ln \frac{N_A N_D}{n_i^2}$ .

So, if you change the material and if you keep dopant concentrations the same and the temperature is also same typically the room temperature. The only thing is changing is  $n_i$  we have seen earlier that  $n_i$  depends upon the band gap square root of  $N_c N_v$  exponential minus  $\frac{E_g}{2kT}$ . So, as the value of the band gap increases  $n_i$  essentially goes down because it's an exponential with a negative term.

If the value of  $n_i$  goes down then the built in potential will essentially increase. So, in this case we have 3 materials. So, I will write down the table that is given in the problem. So, we have germanium, silicon, gallium arsenite. The band gap values are given in eV these are mainly used for just comparison. We do not need the band gap values as far as this problem is concerned, germanium 0.7, silicon is 1.1 gallium arsenite is 1.4. What we do need is the value of  $n_i$  and  $n_i$  is again given for centimeter cube. So, germanium is  $2.4 \times 10^{13}$ , silicon is  $1 \times 10^{10}$  and gallium arsenide is  $2.1 \times 10^6$ .

So,  $n_i$  essentially decreases as the value of the band gap increases. So, we now need to

calculate the built in potential for these 3 materials. We can make use of this formula just substitute  $N_a$  and  $N_d$  and then the values of  $n_i$  for the different materials. So, we can go through and workout the math. I will just write down the final answer. So,  $v_{naught}$  which is your built in potential is nothing but 0.372 the units is words. For germanium, it is higher for silicon 0.775 and it is even higher for gallium arsenide 1.213.


So, as the value of  $n_i$  goes down because you have a higher band gap. The built in potential at the junction essentially increases. So, this information is especially useful when you try to build devices with materials apart from silicon because once you know the built in potential, we will also know what kind of current that needs to be applied to the circuit for a particular kind of application.

(Refer Slide Time: 13:36)


**Problem #3**

A Si abrupt junction in equilibrium at  $T = 300$  K is doped such that  $E_c - E_F = 0.21$  eV in the n region and  $E_F - E_v = 0.18$  eV in the p region. Take  $n_i = 10^{10}$  cm<sup>-3</sup>,  $E_g = 1.10$  eV, and  $E_{Fi} = 0.55$  eV.

- a) Draw the energy band diagram of the junction.
- b) Determine the impurity doping concentrations in each region.
- c) Determine the built-in potential.

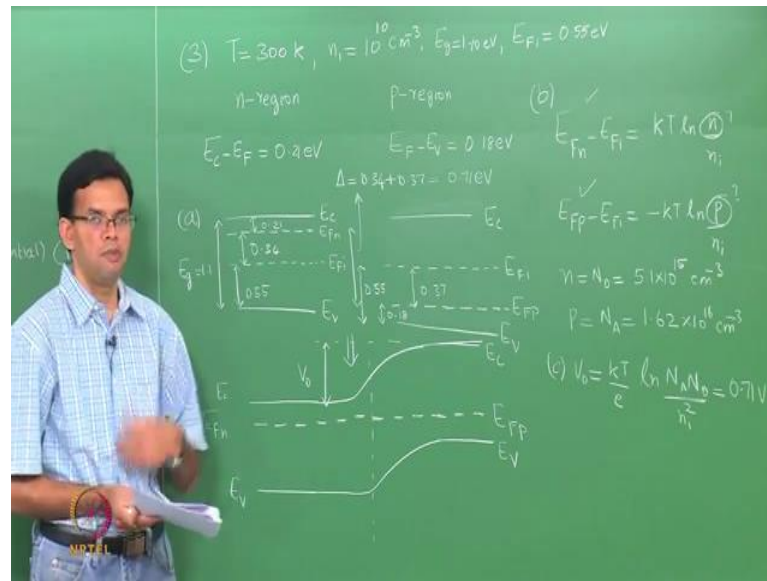


Electronic materials, devices, and fabrication



Let us now go problem 3. In problem 3 we have a silicon abrupt junction which is in internal equilibrium at room temperature.

(Refer Slide Time: 14:00)



This is assignment 5 in assignment 4 we look at metal is 300 kelvin. It is doped in such a way such that  $E_c - E_f$  0.21 electron volts in the N region. So, you have an N region and you have a p region. So, in this question the doping concentrations are not given, but the position of the fermi level is. So, here  $E_c - E_f$  is 0.21 electron volts and  $E_f - E_v$  is 0.18 electron volts the material is silicon. So, you have somehow with the parameters of silicon  $n_i$  which is  $10^{10}$  for centimeter cube. The band gap of silicon  $E_g$  is 1.10 electron volts.

The position of the intrinsic fermi level  $E_{fi}$  it is not exactly at the center, but it is very close to the center. So, we can take this as 0.55 electron volts. So, these are some of the parameters of intrinsic silicon that we can use. So, the first part of the questions says, draw the energy band diagram for the p n junction. So, before we do that, let us have to first draw the energy band diagram for the 2 regions separately. And then we can put them together to draw the energy band diagram for the junction.

So, on the end side this is my conduction band. This is my valence band, this gap is nothing but  $E_g$  which is 1.1  $E_{fi}$  is at the center of the gap. So, that is 0.55 and  $E_g$  is 1.1. So, this question says  $E_c - E_f$  is 0.21. So, the fermi level on the end side  $E_{fn}$  is 0.21 electron volts. So, this height which is nothing but 0.55 minus 0.21 is 0.34. So, all the energies are in electron volts and just not writing the units, everything is in eV.

We can now do the same for the p region. So, the material is the same. So, the band gap

is the same and just draw this slightly better. So, it is the same silicon. So, the  $E_c$  and  $E_v$  are located in the same place  $E_f$  will also be located in the center  $E_f$  in this particular problem  $E_f$  minus  $E_v$  is given to be 0.18 electron volts.

So,  $E_f$  minus  $E_v$  this is 0.18. So,  $E_f$  minus  $E_c$  is 0.55. So, that this height is nothing but 0.37. So, this is 0.55, this is 0.18 this is 0.37. So, we have the energy band diagrams of the N and p regions separately. We can put them together and draw the energy band diagrams of the pn junction, but before we do that I will like to calculate the concentration of electrons and holes on the n and the p side.

So, that we can do by basically using the formula  $E_f$  minus  $E_f$  is  $kT \ln N$  over  $n_i$  and  $E_f$  minus  $E_f$  is equal to minus  $kT \ln$  of  $p$  over  $n_i$ . So, the position of the Fermi level is related to the concentration of the majority carriers on the end side it is your donors on the p side it is the acceptors. So, here this term is known and this is the unknown, same way here this is known and this is unknown.

So,  $E_f$  minus  $E_f$  is 0.34 and  $E_f$  minus  $E_f$  is minus 0.37. So, we can substitute in the values. So, that we get  $n$  equal to  $N_d$  which is equal to 5.1 times 10 to the 15 centimeter cube  $p$  is nothing but  $N_a$  is slightly higher 1.62 times 10 to the 16 for centimeter cube. So, even without doing the numbers we could have predicted that  $N_a$  will be higher than  $N_d$  simply because the Fermi level on the p side is located much closer to the valence band, it is only 0.18.

Compared to the Fermi level on the end side which is 0.21 electron volts below the conduction band. So, we now draw the energy band diagram separately. We also have the concentration of the electrons and the holes. So, let me draw the energy band diagram when the junction is formed. To do that we know that the Fermi levels must essentially line up at equilibrium.

So, this is  $E_f$  n, this is  $E_f$  p far away from the junction. You still have an n type semiconductor and you still have a p type semiconductor. Let me just arbitrarily mark and interface between these 2 and we can show the band bending. So, that these 2 joints. So, this is  $E_b$  this is  $E_c$  this is  $E_c$  and this is  $E_v$ . So, you have the Fermi level lining up and there is a built in potential. This is a straight line and there is a built in potential  $V_{bi}$  found at the junction.

So, part b we need to determine the concentration of the impurities. So, we actually just did that. So, this is essentially part b, just by looking at the shift in the Fermi levels we can calculate the concentration of the impurities. Part c, we want to calculate the built-in potential. So,  $V_{bi}$  is nothing but  $\frac{kT}{e} \ln \left( \frac{N_A N_D}{N_i^2} \right)$ . We can do all the substitutions and the numbers. So, if this works out to be 0.71 volts. We can also calculate the built-in potential by looking at the energy band diagram.

So, in this particular case, the distance between  $E_{fn}$  and  $E_{fp}$ . So, this distance is essentially 0.34 plus 0.37. So, this distance  $\Delta E = 0.34 + 0.37$  which is 0.71 electron volts. So, when the junction is formed we know that the Fermi levels have to line up. So, we can think of as either the n-side shifting completely by 0.71 eV or the p-side shifting up by the same 0.71 eV. So, that they line up. So, the built-in potential or the built-in voltage is nothing but the difference between the Fermi level positions.

So, this is 0.71 eV if you divide by  $e$  it is 0.71 volts. So, instead of using the formula you can also calculate the built-in potential by just looking at the energy band diagram. So, let us now go to problem 4.

(Refer Slide Time: 24:55)

#### Problem #4 cont'd

The length of the p- and n- regions are 5 and 100  $\mu\text{m}$  respectively.

- a) Calculate the minority diffusion lengths and determine what type of diode this is.
- b) What is the built-in potential across the junction?
- c) What is the current when there is a forward bias of 0.6 V across the diode? Take  $T = 300 \text{ K}$ .






(Refer Slide Time: 24:56)


### Problem #4 cont'd

d) Estimate the forward current at 100 °C (373 K) when the voltage across the diode remains at 0.6 V. Assume temperature dependence of  $n_i$  dominates  $D, L$ , and  $\mu$ .

e) What is the reverse current when the diode is reverse biased by a voltage  $V_r = 5$  V?

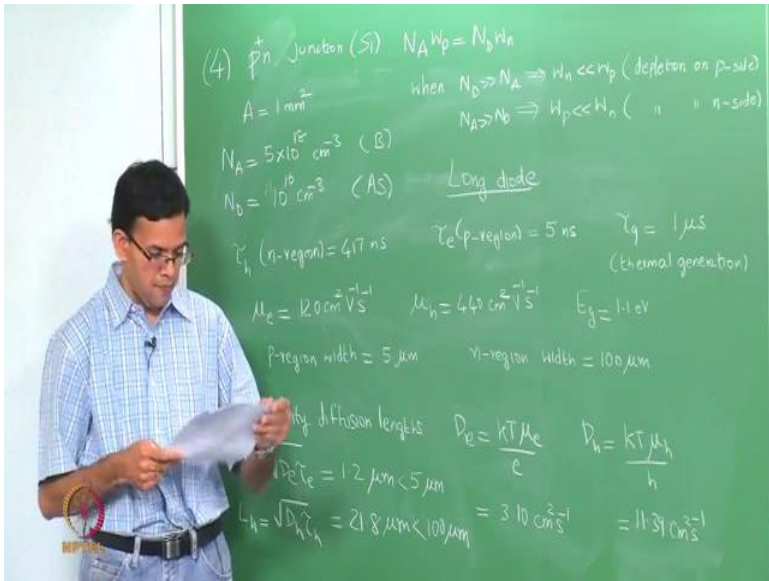


Electronic materials, devices, and fabrication



So, in problems 1 2 3 we looked at the p n junction in equilibrium. So, that there was no external potential, there was applied and no current. There was flowing through the junction, in problem 4 which is slightly a long problem. We are going to look at a p n junction that is essentially bias. And we are going to calculate some values for the current in the forward and the reverse bias. So, problem 4.

(Refer Slide Time: 25:35)



(4)  $p^+n$  Junction (Si)  $N_A W_p = N_D W_n$   
 when  $N_D > N_A \Rightarrow W_n \ll W_p$  (depletion on p-side)  
 when  $N_A > N_D \Rightarrow W_p \ll W_n$  ( " " n-side)  
 $A = 1 \text{ mm}^2$   
 $N_A = 5 \times 10^{18} \text{ cm}^{-3}$  (B)  
 $N_D = 10^{16} \text{ cm}^{-3}$  (AS) Long diode  
 $\tau_n$  (n-region) = 417 ns  $\tau_p$  (p-region) = 5 ns  $\tau_g = 1 \mu\text{s}$  (thermal generation)  
 $\mu_n = 1200 \text{ cm}^2 \text{ V}^{-1} \text{ s}^{-1}$   $\mu_p = 440 \text{ cm}^2 \text{ V}^{-1} \text{ s}^{-1}$   $E_g = 1.1 \text{ eV}$   
 p-region width = 5  $\mu\text{m}$  n-region width = 100  $\mu\text{m}$   
 by diffusion lengths  $D_n = \frac{kT\mu_n}{e}$   $D_p = \frac{kT\mu_p}{h}$   
 $L_n = \sqrt{D_n \tau_n} = 1.2 \mu\text{m} < 5 \mu\text{m}$   $L_p = \sqrt{D_p \tau_p} = 21.8 \mu\text{m} < 100 \mu\text{m}$   
 $\mu_n = 310 \text{ cm}^2 \text{ V}^{-1} \text{ s}^{-1}$   $\mu_p = 11.37 \text{ cm}^2 \text{ V}^{-1} \text{ s}^{-1}$

You have an abrupt p n plus junction. So, when we say p n plus or a N p plus N, the plus essentially denotes that this is heavily a doped. So, when 1 of the carriers or when 1 of

the sides of a p n junction is heavily doped, then the depletion region lies almost entirely on the other side. So, one way to see that is to go back to this equation. So,  $N_a W_p$  is equal to  $N_d W_n$ . So, when  $N_d$  is much greater than  $N_a$ , this implies  $W_n$  is much smaller than  $W_p$ . So, that the depletion width is almost entirely on the p side. I will also just write the reverse when  $N_a$  is much greater than  $N_d$ .

Then you have  $W_p$  much smaller than  $W_n$  and the depletion is almost entirely on the N side. So, we have an abrupt p n junction the cross sectional area  $a$  is 1 milli meter square. We will use to cross sectional area to calculate the current the accepted concentration of 5 times  $10^{18}$  boron atoms on the p side. So,  $N_a$  is 5 times  $10^{18}$  per centimeter cube. And this is boron there is a donor concentration  $N_d$  is  $10^{16}$  per centimeter cube and this is arsenic. So, in this problem  $N_a$  is much higher than  $N_d$ .

So, this should actually read p plus and not p n plus, my mistake because  $N_a$  is much greater than  $N_d$ . So, we have 5 times  $10^{18}$  boron and  $10^{16}$  arsenic atoms on the N side. The whole lifetime values are also given. So, the lifetime of the whole tau h in the N region. So, these are your minority carriers. This is equal to 417 nano seconds. Similarly, the lifetime of the electrons in the p region is only 5 nano seconds.

And this difference is because of the difference in concentration of the dopants. The thermal generation lifetime is also given. So, tau g is 1 micro second. Some other values are also given for this problem. So,  $\mu_e$  which is the mobility of the electrons. So, 120 centimeters square per volts per second,  $\mu_h$  is 440 centimeter square per volts per second,  $E_g$  is 1.1 e v, the length of the p and the n region also given. So, you have a p region width is 5 micro meters and the N region width is 100 micro meters.

So, these are the whole set of data that is given about silicon p n junction. So, the first thing we need to calculate is the minority diffusion length and to determine what type of diode this is. So, we want to calculate the minority diffusion length. So, in the case of the p n junction under equilibrium. We have a dynamic equilibrium. So, that electrons and holes are moving across a junction and constantly get annihilated.

When we apply a forward bias the p side is connected to the positive, the n side is connected to the negative. The energy levels no longer line up, but essentially it gets shifted and when this happens the barrier comes down. So,  $\phi_{built}$  is the built in potential or the barrier during equilibrium. When you apply an external potential, the

barrier is  $v_{naught}$  mine is  $v_{external}$ . When the barrier goes down, we basically have minority carriers moving across the junction. So, we have electrons from the n side moving to the p side, where there minority carriers.

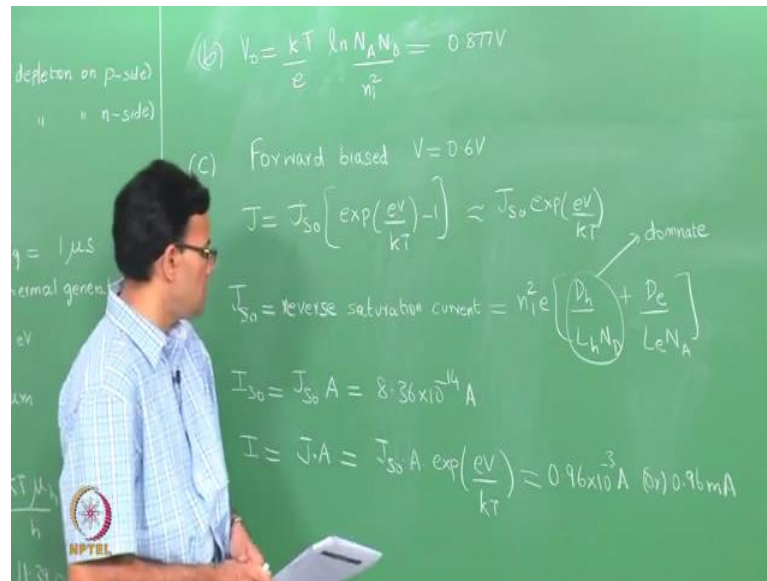
We also have holes from the p side moving to the n side, there they are the minority carriers. So, it is this minority carrier defusion that essentially causes current to flow in a p n junction. So, the first thing we want to calculate is the defusion lengths. To know the defusion lengths we need to know the defusion coefficient. So,  $D_e$  which is the defusion coefficient of the electrons is nothing but  $K T \mu_e$  over  $e$ . So, it depends upon the mobility and  $D_h$  is  $K T \mu_h$  over  $h$ .

So, the values of  $\mu_e$  is given  $\mu_h$  is given everything else is a constant. So, we can plug it in. So, the  $D_e$  is 3.10 centimeter square per second  $D_h$  is 11.39 centimeter square per second. So,  $D_h$  is higher than  $D_e$  because  $\mu_h$  is higher than  $\mu_e$  and this is because the holes are defusing on the inside and the concentration on the inside is 2 orders of magnitude less then the p side. So, because you have the less concetration of your dopents the defusion coefficient are higher from the defusion coefficient.

We can calculate the length. So, one is nothing, but square root of  $d$  times  $\tau$ . So,  $L_e$  is  $d_e \tau_e$   $L_h$  is  $D_h \tau_h$ . So, once again  $D_e$  and  $D_h$  we have calculated  $\tau_e$  and  $\tau_h$  are given. So, we can substitute the numbers. So,  $L_e$  works out to be 1.2 micro meters I am not doing the math. So, all your units are in centimeters. So, your answer will also be in centimeters, you can just convert that into micro meters. So,  $L_e$  is 1.2 and  $L_h$  is larger, it is 21.8 micro meters.

So, if you looked at the length of the diods on the p and the n side. On the n side the diode length is 100, on the p side the diode length is 5 micro meters. So,  $L_e$  is smaller then the 5 micro meters which is the length on the p side  $L_h$  is smaller than 100 micro meters which is the length on the N side. So, that this is essentially a long diode. So, a long diode is 1 in which the diffusion lengths are smaller than the physical lengths of the p and the n region. So, this is part a, let us go to part b. So, in part b we want to calculate the built in potential across the junction.

(Refer Slide Time: 36:12)



So, this is the potential when the junction is in equilibrium. So, this is fairly straight forward. So, just  $kT$  over  $e$   $\ln$  of  $N_A N_D$  over  $n_i$  square. So, we have all the numbers we just need to substitute that this works out to be 0.877 volts. So, this particular problem does not ask you to calculate the depletion width, but you can go ahead and do the calculations. And you will find that the depletion width is almost entirely on the  $n$  side and that there is a very small depletion in width on the  $p$  side.

Part c, what is the current when there is a forward bias of 0.6 volts across the diode. So, now you have the diode to be forward bias the external potential  $v$  is 0.6 volts. So, when we apply an external potential, the barrier height is lowered. So, that there is an increase in current due to the minority carriers diffusing across the junction. In this particular case the current density is given by a constant  $J_{s0}$  times exponential  $\frac{eV}{kT}$  minus 1.

Usually the exponential term is much higher than 1. So, that this can be written as  $J_{s0} \exp\left(\frac{eV}{kT}\right)$ .  $J_{s0}$  is your reverse saturation current. And this is given by  $n_i^2 e \left[ \frac{D_h}{L_h N_D} + \frac{D_e}{L_e N_A} \right]$ . So, we saw the derivation for this during the course notes, but this is your reverse saturation current and this is something that plugs in here. So, if you remember the assignment from the Schottky junction to the metal semiconductor junctions.

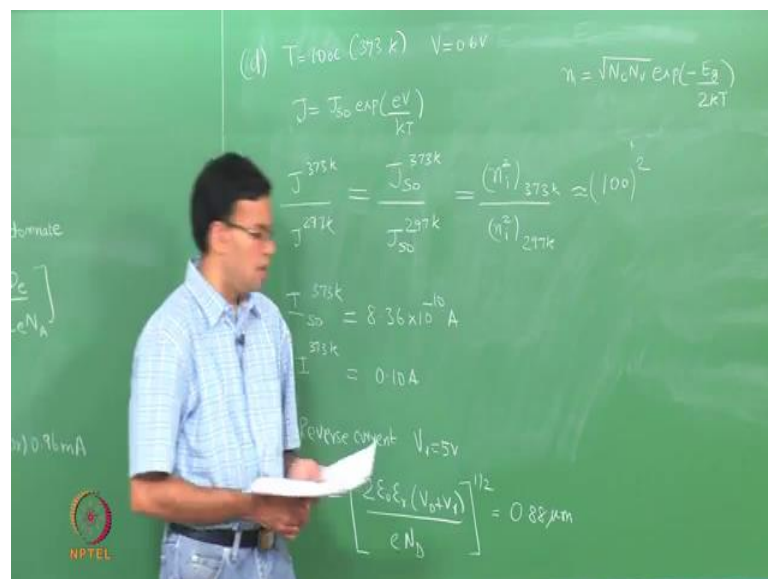
We had a similar expression for this, except that the constant  $J_{s0}$  had a different value

which depended upon the thermionic emission, but now here we have a p n junction. So, the constant here is your reverse saturation current. In this particular problem  $N_A$  is much higher than  $N_D$  and since they are in the denominator this term will essentially dominate over the other term. So, if you this is the reverse saturation current density. To calculate the current we just need to multiply this by the area. So, all the numbers are here we calculated  $D_h$  and  $L_h$  in part a,  $N_A$  and  $N_D$  are known  $n_i$  is also known.

So, that  $J_s$  is naught. So, instead of  $J_s$  is naught, I will directly write  $I_s$  is naught which is  $J_s$  is naught times the area. So, this is  $8.36 \times 10^{-14}$  amperes. So, the reverse saturation current essentially a really small value. Once you know  $I_s$  is naught or  $J_s$  is naught you can calculate the current during forward bias. So, I nothing but  $J$  times  $a$  which is  $J_s$  is naught times  $a$  times exponential  $E_v$  over  $K T$   $v$  is 0.6 that is given. So, the current works out to be  $0.96 \times 10^{-3}$  amperes or 0.96 milli amperes.

So, the current in the forward bias is 0.96 milli amperes. So, that is nearly  $10^{11}$  orders of magnitude or  $10^{10}$  orders of magnitude higher than the reverse saturation current. This is why we essentially call the p n junction to be a rectifier because it conducts very well during forward bias. And the reverse bias current is very small. So, let us now go to part d.

(Refer Slide Time: 41:45)



Part d, we want to estimate the forward current at 100 degrees. So, the temperature is now increased, you can write this in kelvin. So, that is 373 kelvin the voltage is the same. So,

$v$  is 0.6 volts. The question also says that assume the temperature dependence of  $N_i$  dominates over everything else. So, over the diffusion lengths, the diffusion coefficient itself also the mobilities. So, if you only take  $N_i$  into consideration. So, we can see that the current or if you write this down  $J$  is  $J_s$  naught exponential  $E v$  over  $K T$ .

So, ratio of  $J$  at 373 kelvin to that at 293 kelvin this should be 373. So, 373 by 293 kelvin or 297 kelvin which is room temperature. So, let me just draw this, write this 297 is nothing but  $J_s$  naught prime or  $J_s$  naught at 373 kelvin divided by  $J_s$  naught 297 kelvin so the potential is the same. So, the ratio of the currents or the ratio of the current densities is nothing but the ratio of the reverse saturation currents.

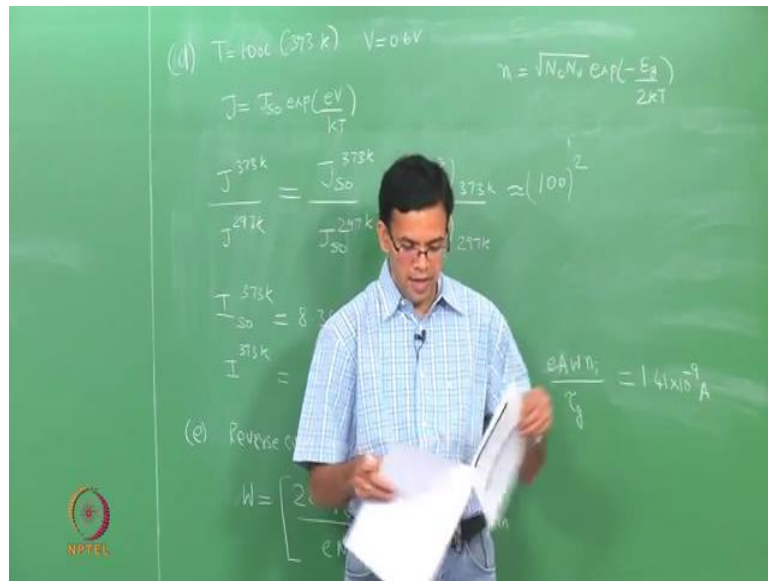
This is directly proportional to  $N_i$  square. So, that this is  $N_i$  square at 373 kelvin divided by  $N_i$  square 297 kelvin,  $N_i$  square is nothing or  $N_i$  square root of  $N_c N_v$  exponential minus  $E g$  over  $2 K T$ . So, for this problem we can take  $N_c$  and  $N_v$  to be independent of temperature. So, the ratio of  $N_i$  is just given by the exponential term. So, if you do this ratio works out to be approximately 100. So, that the reverse saturation current is increased by 100 when we go from room temperature to 100 degrees c.

So, the new values of  $I_s$  naught be 100 square. So, the new values of  $I_s$  naught at 373 kelvin just me write down the final answer that 8.36 times 10 to the minus 10 and current  $I$  at 373 kelvin is 0.10 amps. So, that the current essentially increases by 4 orders of magnitude. In part E, we want to calculate the reverse current. When you have a voltage of 5 volts. So, we want to know the reverse current when  $V_r$  is 5 volts.

To calculate the reverse current we first need to calculate the new width when you apply a reverse bias. So, the width  $w$  is  $2 \text{absoln naught absoln r, } V \text{ naught plus } V_r$  and we said that the depletion region lies almost entirely on the N side. So, I only have  $E$  and  $d$  whole to the half. So, this formula is something we have used before to calculate the width of the depletion region. When you have a p n junction under equilibrium. So, we only modified it to add the reverse bias voltage.

And we also removed the contribution due to  $N_a$  because  $N_d$  is much smaller than  $N_a$ . So, we can plug in the numbers, the new depletion width comes out to be 0.88 micro meters and most of this is in the end side. So, when you have a reverse bias, you have thermal generation of carriers within depletion region. And this thermal generation of carriers is responsible for your reverse current.

(Refer Slide Time: 47:20)





So,  $I_{gen}$  which is the current due to thermal generation of carriers is  $E$  times a cross sectional area times depletion width times  $N_i$  divided by  $\tau_g$ , where  $\tau_g$  is the thermal lifetime of the carriers. In the value is also given. So, everything here is known we can substitute the numbers. In  $I_{gen}$  works out to be  $1.41 \times 10^{-9}$  ampious. So, this number is again much smaller than your forward bias current which is of the order of mili amps. So, once again even if you take thermal generation of carriers into account, we essentially have a rectifying action in a p n junction.

(Refer Slide Time: 48:15)

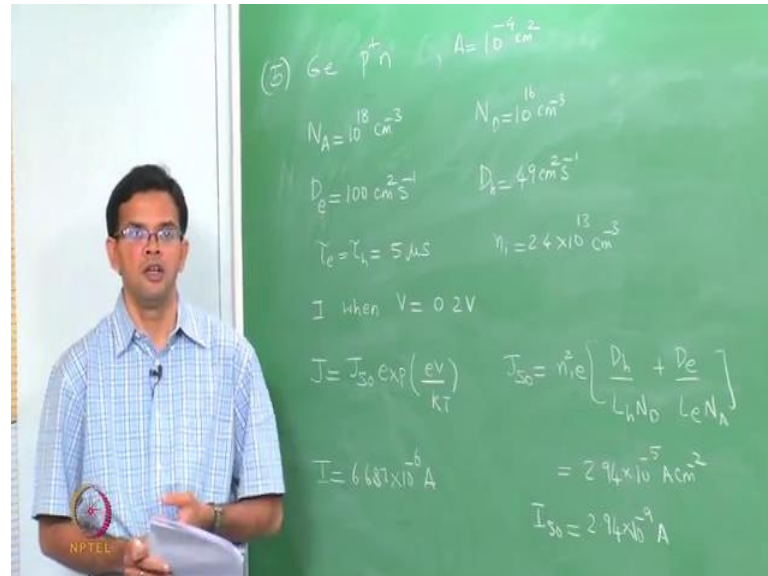
**Problem #5**

A Ge p<sup>+</sup>n diode at  $T = 300$  K has the following parameters:  $N_A = 10^{18} \text{ cm}^{-3}$ ,  $N_D = 10^{16} \text{ cm}^{-3}$ ,  $D_h = 49 \text{ cm}^2\text{s}^{-1}$ .  $D_e = 100 \text{ cm}^2\text{s}^{-1}$ ,  $\tau_h = \tau_e = 5 \mu\text{s}$ , and  $A = 10^{-4} \text{ cm}^2$ . Determine the diode current for a forward bias voltage of  $0.2$  V. Take  $n_i = 2.4 \times 10^{13} \text{ cm}^{-3}$ .


Electronic materials, devices, and fabrication


So, let us now look at the last question. So, problem 5 you have a germanium p n junction diode. So, it is germanium p plus n the values are given.

(Refer Slide Time: 48:38)



So,  $N_A$  is  $10^{18}$  per centimeter cube,  $N_D$  is  $10^{16}$  D h. So,  $D_h$  I will write on this side. So,  $D_h$  is 49 centimeter square per second,  $D_e$  because we are looking at minority carriers that is 100 centimeter square per second,  $\tau_e$  is equal to  $\tau_h$  which is equal to 5 micro seconds. And the cross sectional area is  $10^{-4}$  per centimeter square. So, we want to calculate the diode current. So, we want to calculate  $I$ , when we have a forward bias  $v$  of 0.2 volts  $n_i$  is 2.4 times  $10^{13}$  per centimeter cube. So, this is very similar to the previous question.

So,  $J$  is  $J_s$  naught exponential  $E v$  over  $K T$  and then  $J_s$  naught is  $n_i$  square over  $E d h$  over  $l h N_D$  plus  $D_e$  over  $L_e N_A$ . So, all the numbers are given. So,  $J_s$  naught I will just substitute and write the final answer, but you can directly do the substitution.  $J_s$  naught is 2.94 time  $10^{-5}$  ampier per centimeter square. So, the current  $I_s$  naught is 2.94 times  $10^{-9}$  ampiers. Once you know  $I_s$  naught, you can substitute here and you can get the current.

The current  $I$  is noting but 6.687 times  $10^{-6}$ . So, in this particular case, the difference between the current and  $I_s$  naught is not as high as in the case of silicon. One particular reason is because your applied voltage is very small. It s only 0.2 volts. Another difference is that the material is germanium. So, that the band gap is smaller. So,



the built-in potential is also smaller at the same time  $N_i$  is larger. So, that  $J_s$  is also larger. So, these are some of the factors, you have to take into account when choosing materials performing p-n junction.